

# FINAL CALL FOR PAPERS

11<sup>th</sup> International Conference on Optics-photonics

Design & Fabrication



“ODF '18, Hiroshima”  
November 28<sup>th</sup>-30<sup>th</sup>, 2018



International Conference Center Hiroshima

Organized by

Optics Design Group of The Optical Society of Japan

Co-sponsored by

JSAP (The Japan Society of Applied Physics)

The City of Hiroshima

Hiroshima Convention & Visitors Bureau

In cooperation with

ICO (International Commission for Optics) • EOS (European Optical Society) • SPIE (The International Society for Optics and Photonics) • TPS (Taiwan Photonics Society) • OSA (The Optical Society) • OSK (Optical Society of Korea) • OPSS (Optics and Photonics Society of Singapore) • ROS (Rozhdestvensky Optical Society) • PIDA (Photonics Industry & Technology Development Association) • TOOMA (Taiwan Optics/Optronics Manufacturers' Association) • DGaO (German Society of Applied Optics) • The 179<sup>th</sup> Committee on Photonics Information Systems, JSPS (Japan Society for the Promotion of Science) • Applied Optics Meeting in Kansai • The Astronomical Society of Japan • The Color Science Association of Japan • IEICE (The Institute of Electronics, Information and Communication Engineers) • IEIJ (The Illuminating Engineering Institute of Japan) • IIEEJ (The Institute of Image Electronics Engineers of Japan) • JIEP (Japan Institute of Electronics Packaging) • JOEM (Japan Optomechatronics Association) • JOMA (Japan Optical Measuring Instruments Manufacturer's Association) • JPS (The Physical Society of Japan) • JSMBE (Japanese Society for Medical and Biological Engineering) • JSPE (The Japan Society for Precision Engineering) • LSJ (The Laser Society of Japan) • OITDA (Optoelectronics Industry and Technology Development Association) • The Spectroscopical Society of Japan • SPLJ (The Society of Photography and Imaging of Japan)



(Some of above cooperative organizations are under negotiation.)

## INTRODUCTION

The 11th International Conference on Optics-photonics Design and Fabrication, “ODF'18, Hiroshima”, will be held at the International Conference Center Hiroshima, Hiroshima, Japan on November 28th-30th, 2018. Optics-photonics design and fabrication will continue to play a significantly important role in the future, achieving harmony between technology and the environment and building bridges for real international cooperation worldwide. ODF'18 provides an international forum for original paper presentations and discussions of optics-photonics design and fabrication-related technological and scientific topics, including theory, design, fabrication, testing, applications and others.

## SCOPE OF THE CONFERENCE

ODF'18 is an international forum for the engineers and scientists in the field of Optics-photonics Design and Fabrication to exchange their ideas and achievements with the goal of future mutual progress. The conference covers the following major topical categories;

## CATEGORIES AND PRELIMINARY LIST OF INVITED SPEAKERS

### Plenary

I. Ishii (Hiroshima Univ. / Japan)

*"High-Speed Tracking Optical Devices and Their Applications"*

J. Rolland (Univ. of Rochester / USA)

*"The Emergence of Freeform Optics: Design for Manufacture"*

### Special Session:

#### “Optics and Photonics for Intelligent Vehicles”

Y. Dzialowski (Argo AI / USA)

*"New Advances in Single Photon LiDARs and Application for Driverless Cars"*

Y. Iwashita (Mazda / Japan)

*"Evolution of Automotive Safety Technology Supported by Optical Devices"*

R. Schäfer (formerly Philips / Germany)

*"Automotive Lighting in the Next Decade: Challenges and Opportunities"*

S. Sekiya (Nippon Seiki / Japan)

*"2-Plane Head-Up Display by Using Single DLP-PGU"*

### Category 1. Optical Design / Simulation

J. Howard (NASA Goddard Space Flight Center / USA)

*(under negotiation)*

*"Optical Design of Space telescopes with Freeform Optics"*

K. Kisamori (AIST, NEC-AIST / Japan)

*"Combining Machine Learning with Simulation: Its Application to Telescope Stray Light Analysis"*

J. Miñano (Univ. Politécnica de Madrid / Spain)

*"Freeform Optics for Virtual Reality"*

U. Zeitner (Univ. Jena / Germany)

*"Microoptical Free-Forms: Design and Fabrication"*

### Category 2. Optical Components / Devices

A. Erdmann (Fraunhofer IISB / Germany)

*"Understanding and Optimization of Imaging for EUV Lithography"*

B. Kress (Microsoft HoloLens / USA)

*"Optical Challenges for Next Generation Mixed Reality Headsets"*

N. Quack (EPFL / Switzerland)

*"Micro- and Nanostructuring of Single Crystal Diamond for Photonic Applications"*

D. Tsai (Academia Sinica / Taiwan)

*"Meta-Lens: Fabrication, Design and Applications"*

### Category 3. Optical Systems

C. Buisset (National Astronomical Research Inst. of Thailand / Thailand)

*"The Evanescent Wave Coronagraph: Design, Performance, and Perspectives for Ground and Space Based Observations"*

S. Hiura (Hiroshima City Univ. / Japan)

*"Computational Imaging: Optics Designed as Primary Image Processor"*

W. Osten (ITO Stuttgart / Germany)

*"Different Approaches for Resolution Enhancement in Optical Micro and Nano Metrology"*

S. Tyo (The Univ. of New South Wales Canberra / Australia)

*"Designing Channel Structures in Multi-Domain Modulated Polarimeter"*

### Category 4. New Technologies

F. Capasso (Harvard Univ. / USA)

*"Flat Optics: from Metalenses to Structured Light"*

C. Denz (Westfälische Wilhelms-Univ. Münster / Germany)

*"To be determined"*

Paper Submission: February 1st–June 30th, 2018 (Extended) <http://www.odf.jp/>

W. Kim (Honam Univ. / Korea)

"Investigation to Achieve Higher Resolution in STED Nanoscopy"

T. Lu (National Taiwan Normal Univ. / Taiwan)

"Structured Light Generated by Vortex Plates and Spatial Light Modulators"

K. Matsushima (Kansai Univ. / Japan)

"Very Large-Scale Computer-Generated Hologram for 3D Display"

The list of invited speakers will be updated in the ODF'18 website.

## PREPARATION OF ABSTRACTS AND MANUSCRIPTS

A limited number of original contributed papers covering unpublished work will be accepted for presentation. Authors are required to submit papers including 35-word abstracts and 2-page manuscripts in the prescribed form. The form can be downloaded from the conference website. Papers must be submitted online. Please see the ODF'18 website for details of the submission procedure. Authors are required to agree to copyright transfer by including a completed form when submitting papers.

### ● 35-word Abstracts

35-word abstracts in an ASCII text file are strictly required and the program committee may automatically modify the abstract that contains over 50 words. Please confirm the number of words using a word counting tool. Also, please avoid the use of scientific and engineering symbols in the abstract. If your paper is accepted, the abstract will appear in the Advance Program.

### ● 2-page Manuscripts

2-page camera-ready manuscripts including text, figures, tables and references must be typed single-spaced on A4 or letter size pages with the title followed by the author's name, affiliation, and address. Accepted papers will be published in the Technical Digest of the conference. For the layout of the manuscript, please see the guidelines on the ODF'18 website.

## ● Abstracts&Manuscripts will be accepted: February 1st-June 30th, 2018(Extended)

For inquiries, please contact:

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The presentation schedule will be determined after the program committee has reviewed the papers. Authors will be notified by August, 2018 whether their papers have been accepted. Notification will be sent to the author listed first by e-mail or letter. Note that it will be the author's responsibility to obtain any necessary and appropriate clearances from his/her affiliated organization.

## ADDITIONAL INFORMATION

### ● Post-Deadline Papers

Detailed information will be announced in the Advance Program and on the ODF'18 website.

### ● ODF'18 Special Issue of OPTICAL REVIEW

The presented papers can be resubmitted and published in the ODF'18 special issue of OPTICAL REVIEW after peer review. It is the English-language journal of the Optical Society of Japan (OSJ). Application forms for the special issue will be presented on the website.

Collaboration and Competition make progress.

For more information please visit the website:

<http://www.odf.jp/>

Join us at *ODF'18, Hiroshima, Japan!*

## REGISTRATION

### ● Registration Fee

The registration fee includes admission to technical

sessions and one copy of Technical Digest. As for the person who paid the registration fee, the reception fee is free.

Type	Before / on (Oct. 28th, 2018)	After (Oct. 28th, 2018)
Member[*]	JPY 40,000	JPY 45,000
Non-Member	JPY 45,000	JPY 50,000
Student	JPY 5,000	JPY 10,000
Accompanying person	JPY 10,000	JPY 10,000
Additional copy of technical digest	JPY 10,000	JPY 10,000

[\*] Member of sponsor and cooperative society  
JPY: Japanese Yen

### ● Registration

Participants in ODF'18 are required to register in the online registration page. The deadline for advanced registration is October 28th, 2018. Online registration: <http://www.odf.jp/registration.html>

### ● Accompanying persons

Participants can register accompanying persons. Accompanying persons are his/her family members. Registration fee for accompanying persons includes all expenses except admission to the technical session, conference pack and one copy of the Technical Digest, but cannot participate in the conference.

### ● Cancellation Policy

There will be no refunds for the registration fee.

## CONFERENCE SITE

ODF'18, Hiroshima, will be held at the International Conference Center Hiroshima within Hiroshima Peace Memorial Park.

Access:

[http://www.pcf.city.hiroshima.jp/icch/e\\_access.html](http://www.pcf.city.hiroshima.jp/icch/e_access.html)

## HOTEL RESERVATION

### ● Hotel

Some hotels in Hiroshima City are arranged for ODF'18 participants. Online hotel reservation system will be available on our website.

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(Some of above committee members are under negotiation.)